

AS-MASTER

RTP tool for production of LEDs

- InGaN annealing
- Contact alloying
- Sapphire , GaAs, InP
- 3x4" and 6" capability
- Automatic loading



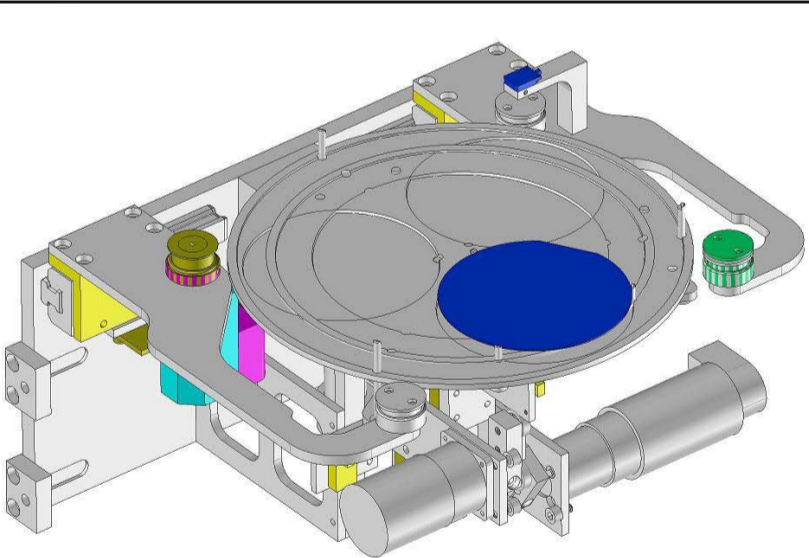
ANNEALSYS

Extended pyrometer control range: 150 C to 1400 C

Full automation for multi substrate loading

Edge pyrometer for enhanced temperature control of compound semiconductors and sapphire substrates processing with susceptor.

SPECIFICATIONS



Stainless steel cold wall chamber technology:

- High cooling rates and low memory effect
- High process reproducibility
- Ultra clean and contamination-free environment

Extended temperature range:

- Room temperature up to 1400 C

High reliability and low cost of ownership
Manual loading version for R&D

RTCVD capability

High vacuum version (10^{-6} mbar) is available

